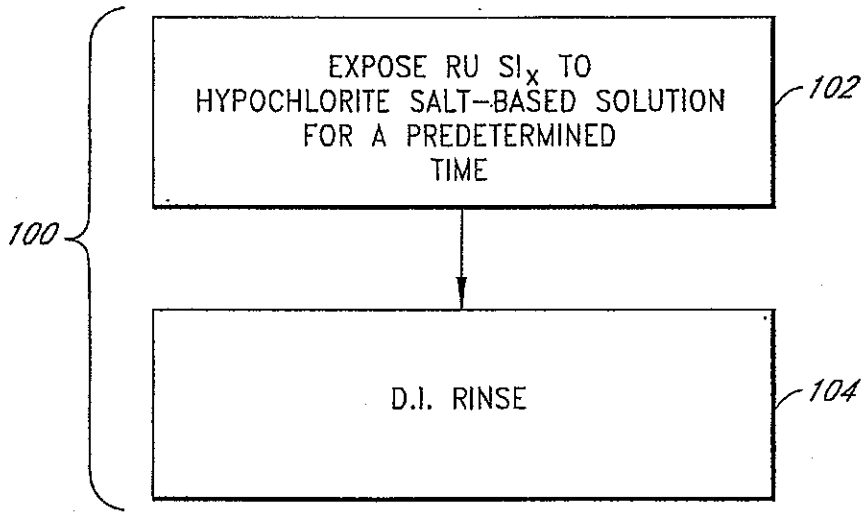

EXPOSE RU SI_X TO HYPOCHLORITE SALT-BASED SOLUTION FOR A PREDETERMINED TIME
102
100
D.I. RINSE
104

FIG. 1

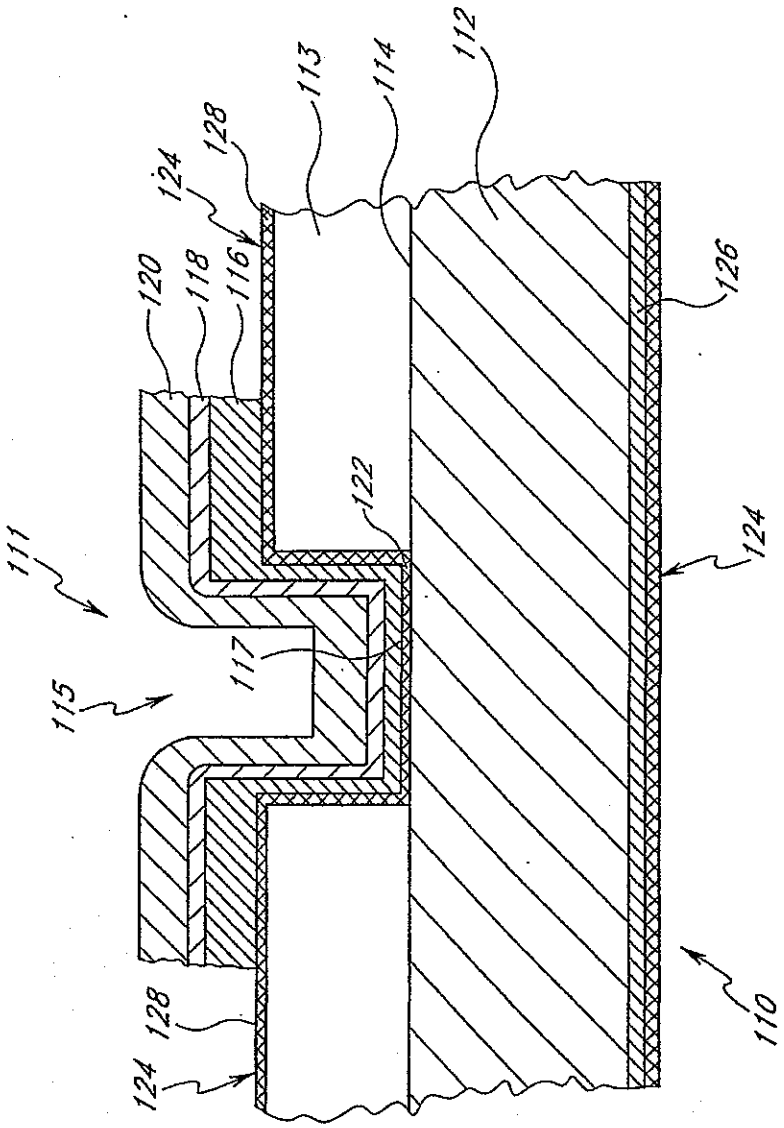

112
113
114
128
124
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122
111
124
117
115
128
124
110

FIG. 2

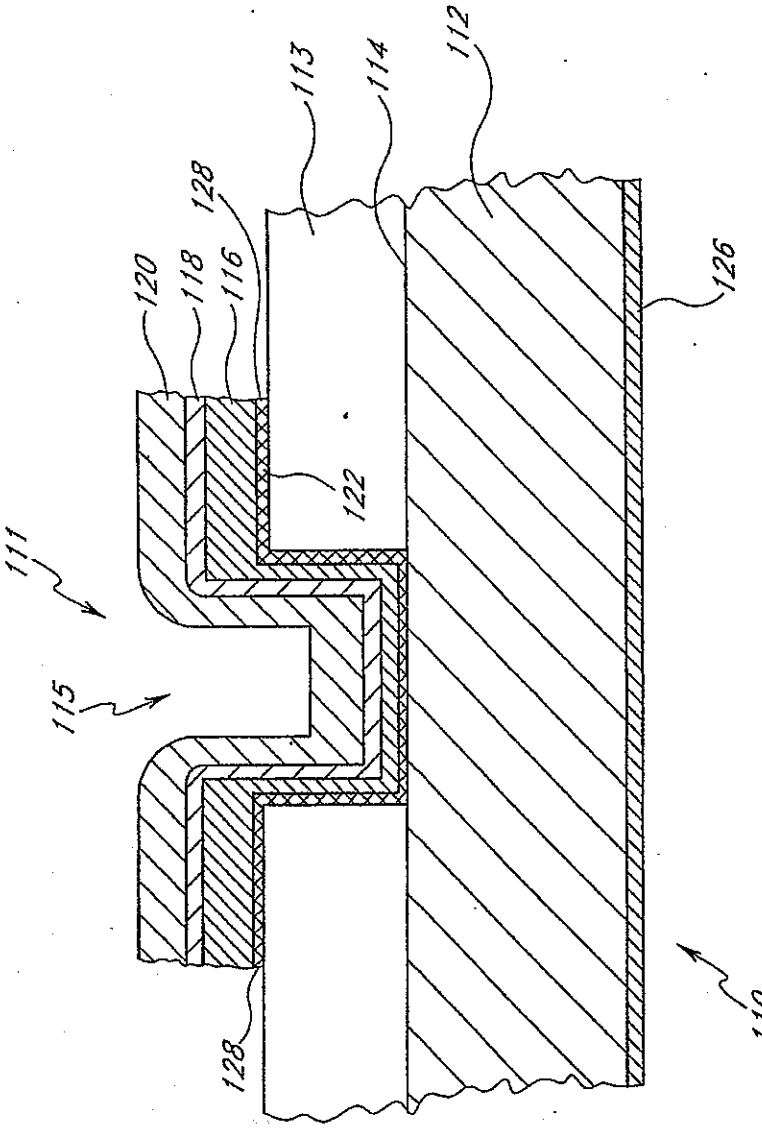
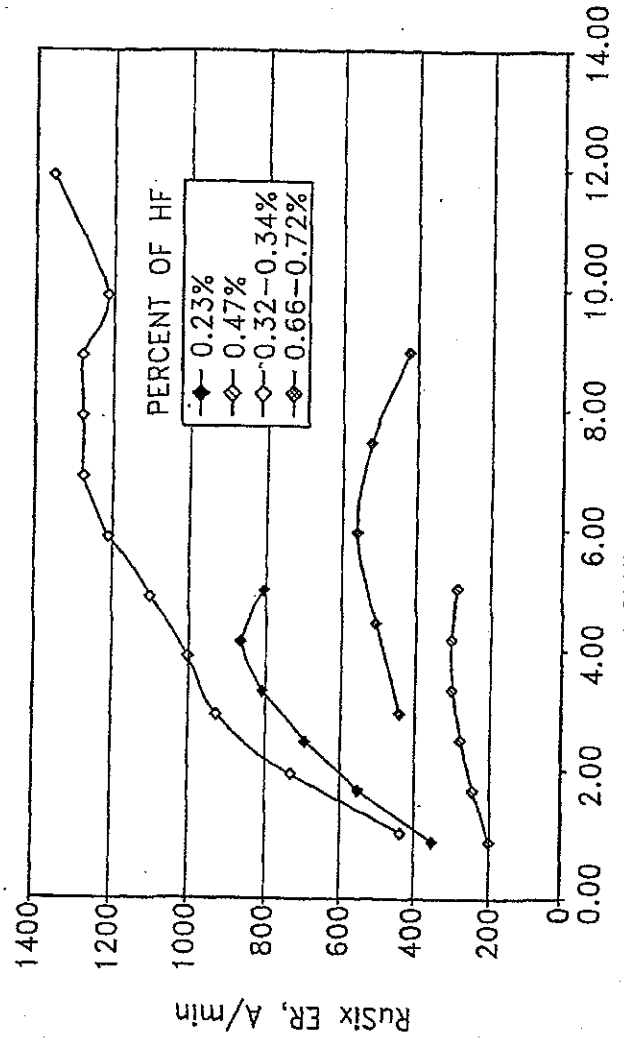


FIG. 3



ETCH RATE vs. KOCl VOLUME PORTION FOR FOUR DIFFERENT HF CONCENTRATIONS

FIG. 4

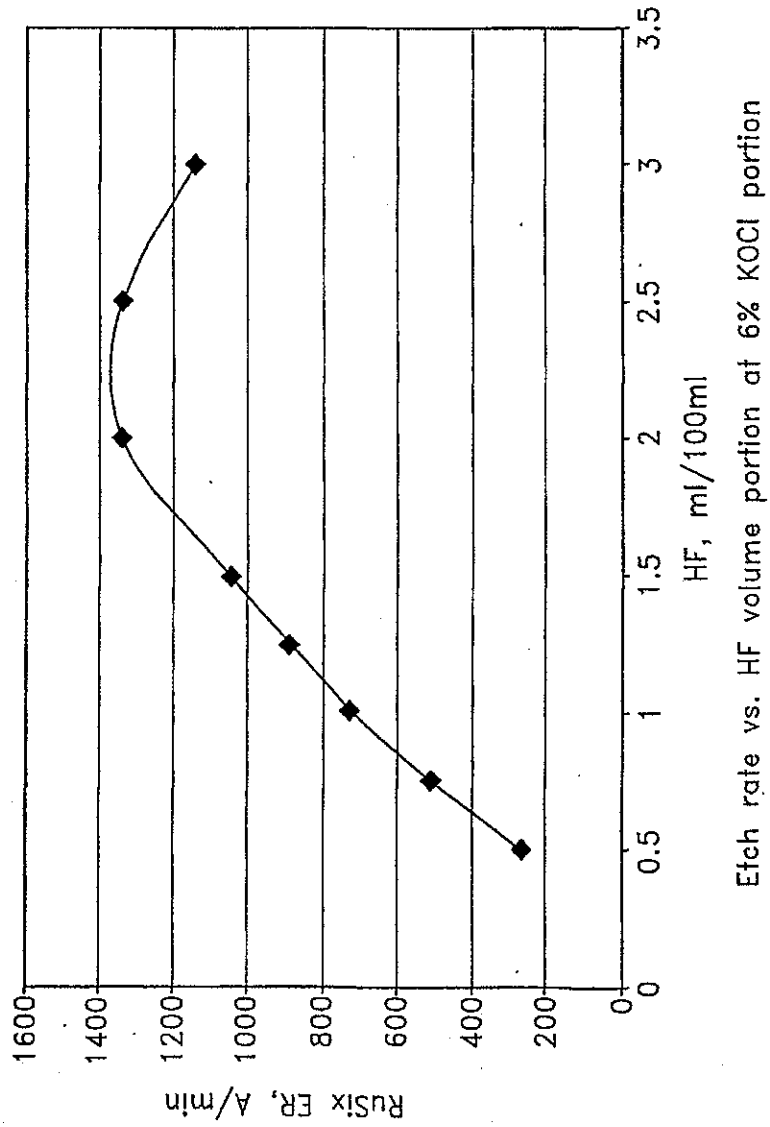

RuSix ER, A/min
1600
1400
1200
1000
800
600
400
200
0
0
0.5
1
1.5
2
2.5
3
3.5
HF, ml/100ml
Etch rate vs. HF volume portion at 6% KOCl portion

FIG.5